Form PTO-1449 | Sheet 1 of 4

Applicant: Fernando Gonzalez, et al. | Confirmation No.: 7257

Serial No.: 10/804,477 | Att'y Docket No.: 11675.22.2.1.3.1

Filing Date: March 19, 2004 | Group: 2812

For: METHOD OF MAKING VERTICAL DIODE STRUCTURES

INFORMATION DISCLOSURE CITATIONS MADE BY APPLICANT

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Examiner Initial*	Document Number	Issue Date	Name
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CLASS SUB CLASS

Examiner: Michelle Estrada | Date Considered: 10/14/04

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Class 3 Sub Class 4

	18	5,162,245	11/10/1992	Favreau
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Examiner: Michelle Estrada Date Considered: 10/14/04

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(including author, title, pertinent pages, etc.)

Examiner Initial*

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While the filing of Information Disclosure Statements is voluntary, the procedure is governed by the guidelines of Section 609 of the Manual of Patent Examining Procedure and 37 C.F.R. §§ 1.97 and 1.98. To be considered a proper Information Disclosure Statement, Form PTO-1449 shall be accompanied by a copy of each listed patent or publication or other item of information and a translation of the pertinent portions of foreign documents (if an existing translation is readily available to the applicant), an explanation of relevance of each reference not in the English language, and should be submitted in a timely manner as set out in MPEP Sec. 609.

Examiners will consider all citations submitted in conformance with 37 C.F.R. § 1.98 and MPEP Sec. 609 and place their initials adjacent the citations in the spaces provided on this form. Examiners will also initial citations not in conformance with the guidelines which may have been considered. A reference may be considered by the Examiner for any reason whether or not the citation is in full conformance with the guidelines. A line will be drawn through a citation if it is not in conformance with the guidelines AND has not been considered. A copy of the submitted form, as reviewed by the Examiner, will be returned to the applicant with the next communication. The original of the form will be entered into the application file.

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The reference designations "A1," "A2," etc. (referring to Applicant's reference 1, Applicant's reference 2, etc.) will be used by the Examiner in the same manner as Examiner's reference designations "A," "B," "C," etc. on Office Action Form PTO-1142.

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